

Doc. No.: NR111130E

The Launch of a Single Wafer Cleaning System That Realizes World's Best Productivity

Kyoto, Japan – November 30, 2011 – Dainippon Screen Mfg. Co., Ltd. has developed the scrubber type* SS-3200 single wafer cleaning system, which realizes world's best** productivity thanks to a perfect balance of high-speed cleaning capacity (up to 800 wafers per hour) and highly stable processing. The SS-3200 scrubber is the answer to the manufacturing needs of next-generation semiconductors. The initial release of the SS-3200 is scheduled for December 2011.

In order to support the miniscule size of electronic parts installed in compact, high-performance electronic terminals such as smartphones and tablet PCs, the latest semiconductor devices are miniaturized to have circuit line widths at the 10 nanometer (one-hundred millionth of a meter) level, as well as multi-layer circuits. For this reason, the demand for scrubber wafer cleaning systems is increasing among device manufacturers so as to improve yield with better cleaning performance in addition to improving streamlining of manufacturing processes by leveraging the systems' high-speed operation.

To accommodate these industry trends, Screen has developed the SS-3200, a single wafer cleaning system that realizes world's best productivity. The SS-3200 features superior cleaning capacity and processing performance based on high stability. This system adopts our newly developed rapid wafer transfer system as well as a totally new control program, which enables a practical processing capacity of 800 wafers per hour (approximately twice as fast as our conventional model) without any increase in the number of cleaning chambers. In addition, while the SS-3200 inherits the highly acclaimed processing performance and the compact 8-chamber design of our best-selling SS-3100 wafer cleaning system, it also supports the miniaturization and multi-layering of semiconductor devices. Furthermore, the SS-3200 has excellent operability, allows for easy maintenance, and is a highly cost-efficient model that contributes to the reduction in energy consumption—a common challenge when manufacturing processes become more complex and there is a consequent increase in the number of steps.

Screen aims to enrich its next-generation cleaning system lineup starting with the SS-3200 and will respond to the wide-ranging customer needs for diverse, energy-saving, and advanced products. As a leading company in semiconductor cleaning systems, Screen will continue to deliver world-class products and contribute to the development of the industry.



SS-3200

Please download the photo from
www.screen.co.jp/eng/press/nr-photo_2009-2011.html

* Scrubber type

A type of wafer cleaning method in which wafers are physically cleaned using soft brushes and deionized water.
This cleaning method is suitable for cleaning processes that only use deionized water.

** As of November 2011 (according to Screen's research).

Note: The SS-3200 will be on display at SEMICON Japan 2011, held at Makuhari Messe in Chiba from December 7 (Wednesday) to 9 (Friday).